

Supporting information

Grafting conductive polymers on graphene oxide through cross-linker: a stepwise approach

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1. Structure Analysis

Table S1. Quantitative comparison of detected elements from XPS spectra

Sample	Element (at.%)			
	C	O	N	S
GO 3	81.1	11.0	6.5	1.6
GO 2	76.6	17.5	4.1	1.2
GO 1	71.9	25.6	2.4	--

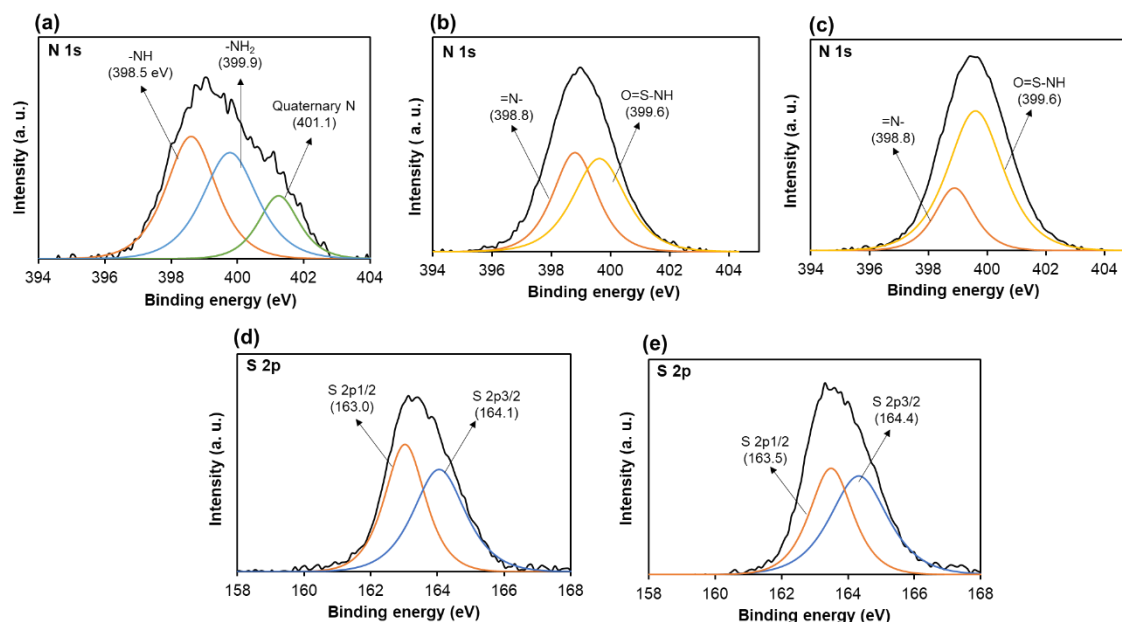
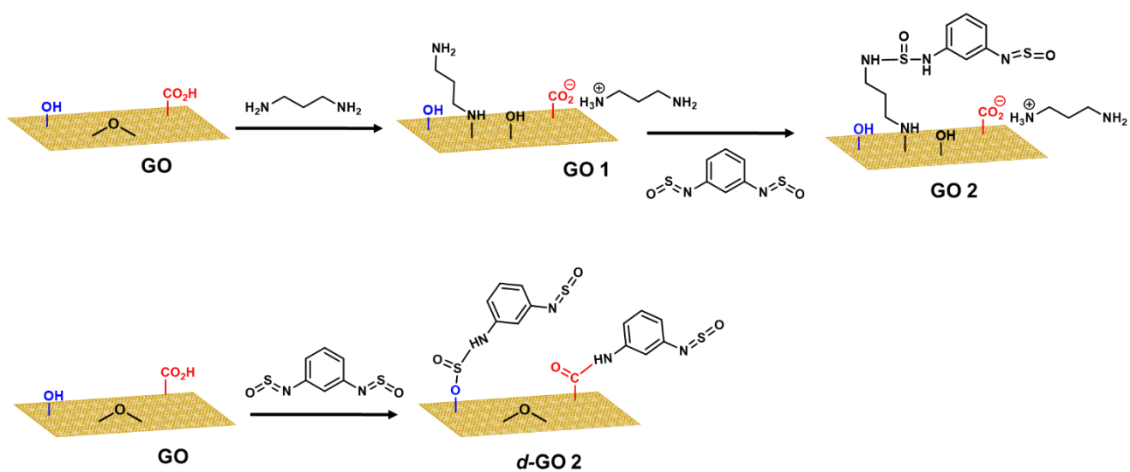


Fig. S1. Narrow scan XPS spectra of (a) N 1s of (a) GO 1, (b) GO 2, (c) GO 3 and S 2p of (d) GO 2, and (e) GO 3

Comparison of GO 2 and *d*-GO 2

The direct reaction of the meta monomer on GO, without 1,3-diaminopropane as a cross-linker, was prepared by the same procedure, except the starting material was GO instead of **GO 1**. The elemental composition of *d*-GO 2 (without using 1,3-diaminopropane) and **GO 2** (addition of 1,3-diaminopropane) was also measured by XPS analysis, as presented in Fig. S 3. In the case of *d*-GO 2, the direct addition of monomer to GO caused the decomposition of the monomer, which might be due to the effect of the carboxylic group of GO [1,2]. In the case of **GO 2**, most of the carboxylic group was neutralized by 1,3-diaminopropane in the first step, which prevented the decomposition of monomer. Therefore, this result confirmed that the addition of 1,3-diaminopropane in the first step is important.



Scheme S1. Synthesis of **GO 2** and **d-GO 2**

Table S2. Quantitative comparison of detected elements from XPS spectra

Sample	Element (at.%)			
	C	O	N	S
GO 2	76.6	17.7	4.1	1.2
d-GO 2	76.4	15.5	6.9	1.1

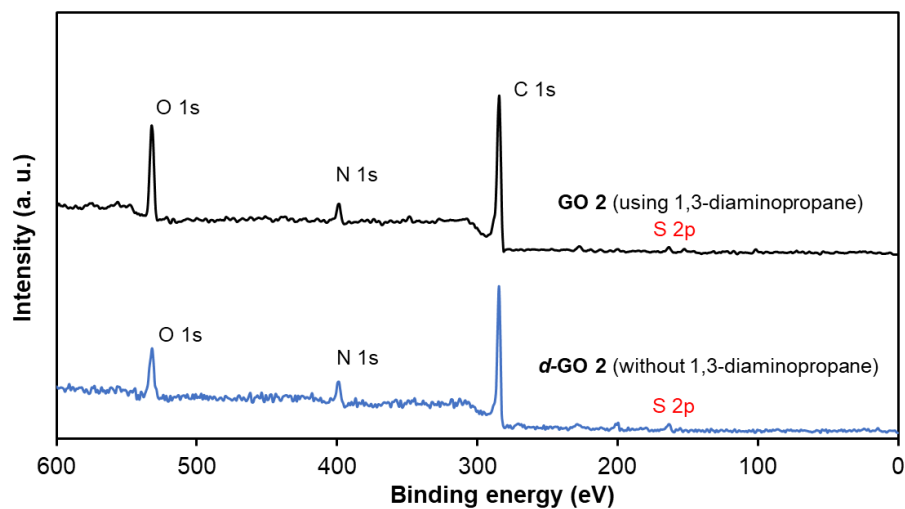
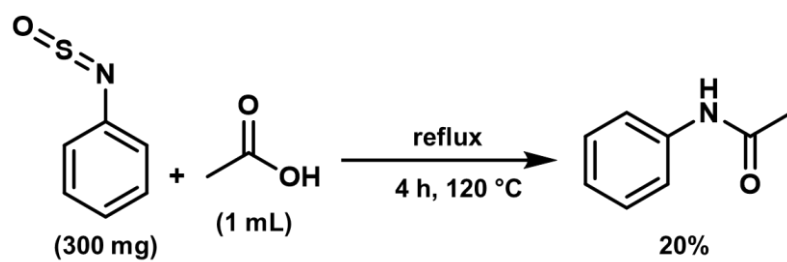


Fig. S2. Wide scan XPS spectra of **GO 2** (functionalization using 1,3-diaminopropane) and **d-GO 2** (functionalization without using 1,3-diaminopropane)



Scheme S2. Possible side reaction between the monomer and carboxylic acid of GO.

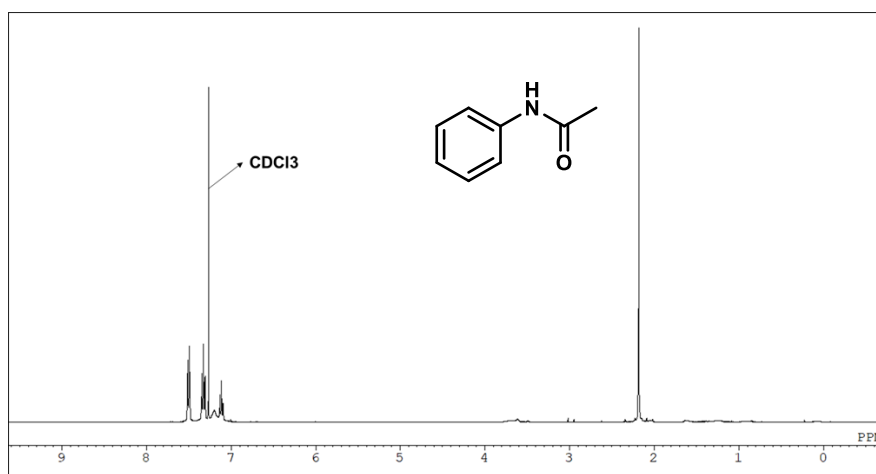


Fig. S3. ^1H NMR spectra of the product of Scheme S3.

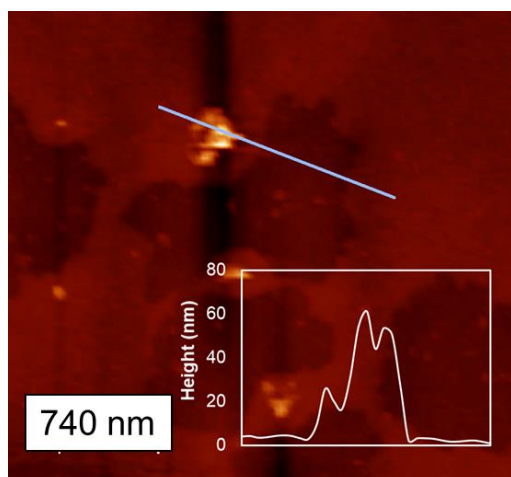


Fig. S4. AFM analysis of just mixing of polymer and graphene

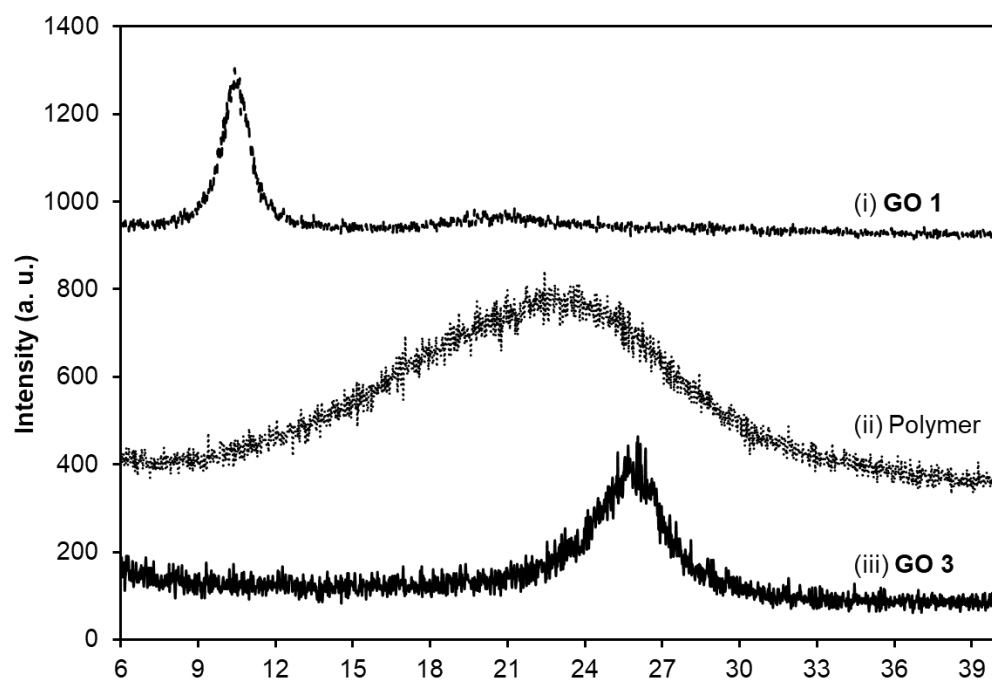


Fig. S5. XRD pattern of (i) GO 1, (ii) polymer, and (iii) GO 3

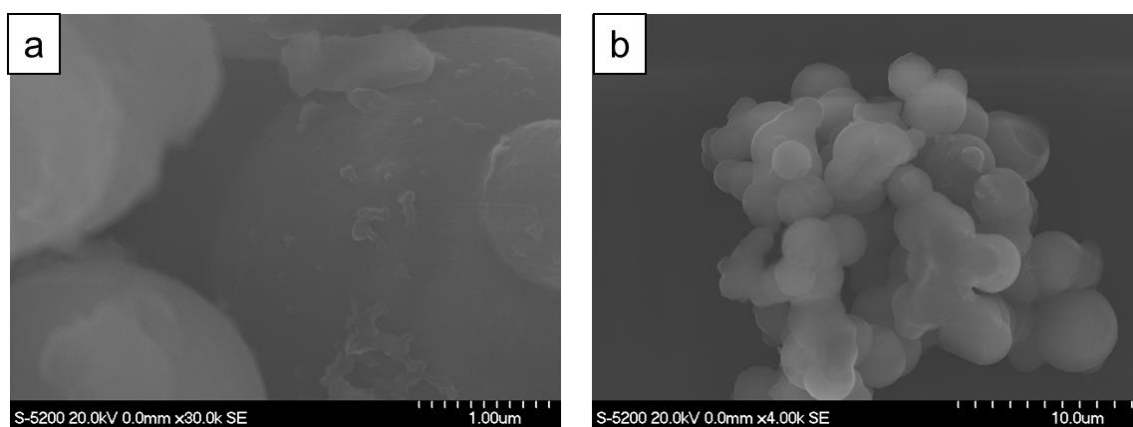


Fig. S6. SEM images of polymer (a) high resolution and (b) low resolution.

2. Electrochemical analysis

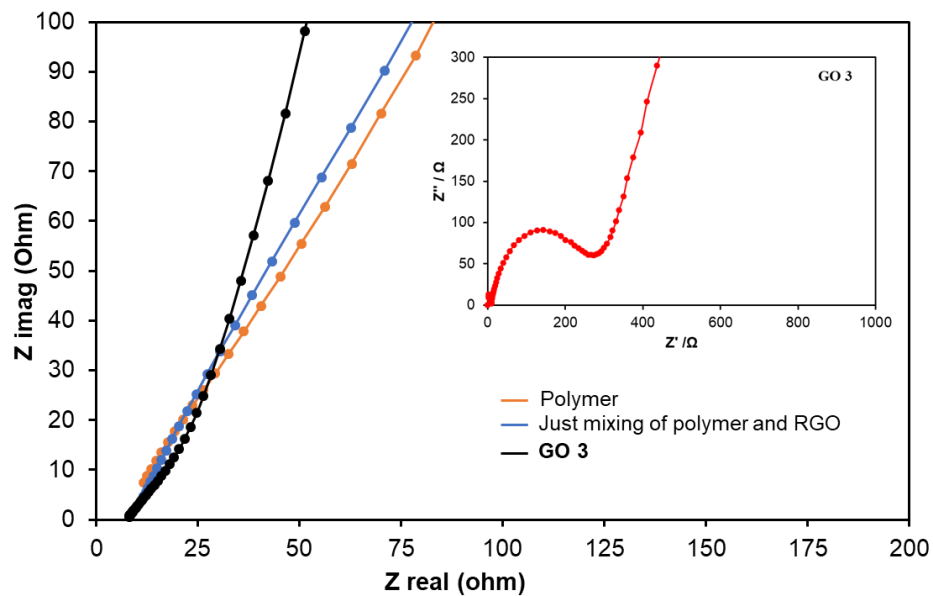


Fig. S7. Nyquist plots of GO 3, just mixing of polymer and graphene and only polymer. Inset is the high-frequency plot for GO 3.

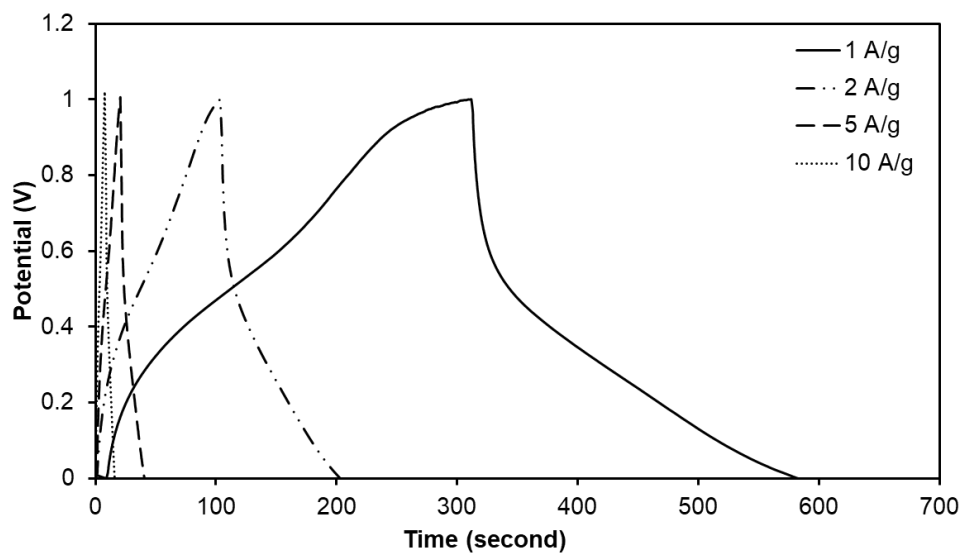


Fig. S8. Galvanostatic charge/discharge curve of GO 3 at a current density of 1, 2, 5, and 10 A g⁻¹.

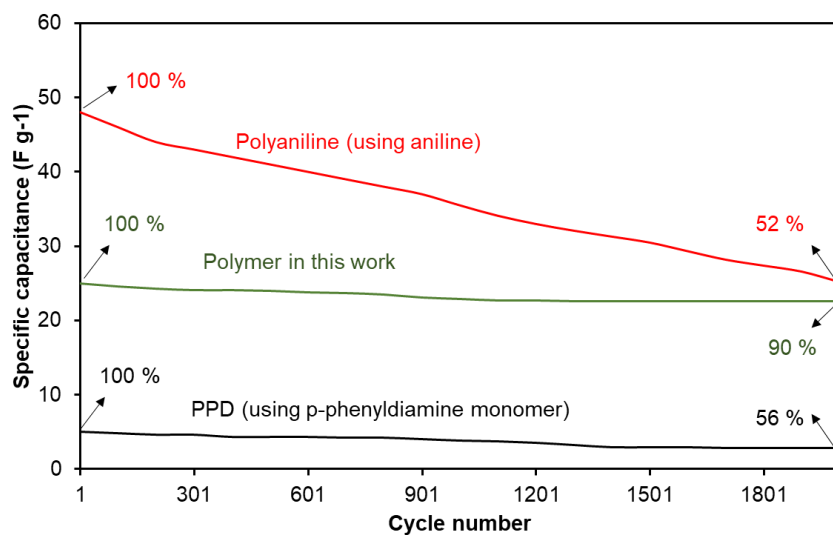


Fig. S9: Cycling stability test of different polymer at a current density of 2 A g^{-1}

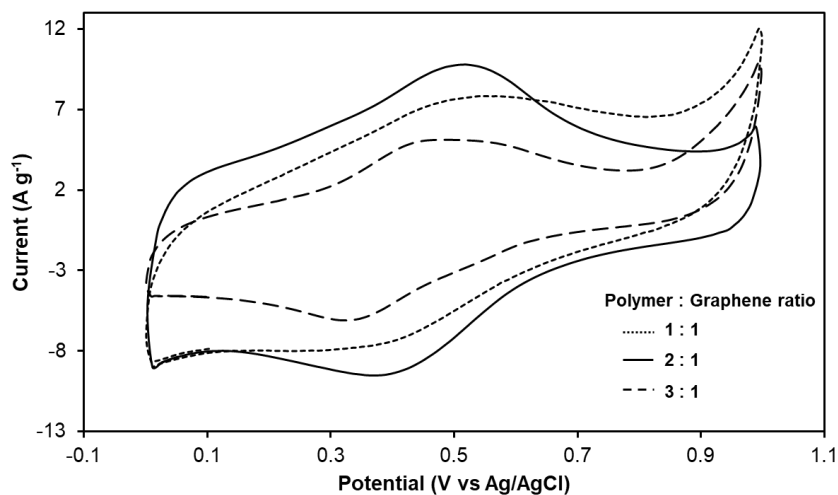


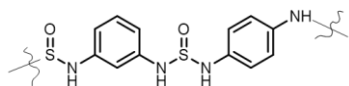
Fig. S10: CV study of GO 3 with different mass ratios of polymer to graphene at a scan rate of 50 mVs^{-1} .

3. Elemental analysis

Table S3. Quantitative comparison of detected elements from EDS analysis of **GO 3** (different ratios of polymer/graphene).

Polymer:GO (wt ratio)	Element (at%)				Polymer content (wt%)*
	C	O	N	S	
1 : 1	77.7	13.5	6.2	1.2	13.3
2 : 1	80.6	12.0	5.2	1.8	19.9
3 : 1	83.4	10.8	4.3	2.4	26.6

* Polymer contents were calculated based on the molecular weight of the unit and sulfur content. Unit structure for calculation is as follows:



4. Comparison of supercapacitor performance in three-electrode systems

Table S4. Comparison of supercapacitor performance in three-electrode systems.

Material	Cycle number	Capacity retention	Measurement conditions	References
PANI-G	1500	90%	10 A g ⁻¹	[3]
PANI-G	1000	91%	2 A g ⁻¹	[4]
PANI-G	1500	80%	0.5 A g ⁻¹	[5]
PANI-G	200	96%	3 A g ⁻¹	[6]
PANI-G	1000	85%	0.5 A g ⁻¹	[7]
Ppy-G	1000	92%	1 A g ⁻¹	[8]
Ppy-G	200	93%	5 A g ⁻¹	[9]
Ppy-G	1500	71%	50 mV s ⁻¹	[10]
PEDOT-G	1000	88%	0.3 A g ⁻¹	[11]
PEDOT-G	2000	87%	0.5 A g ⁻¹	[12]
Ppy-G	500	90%	100 mVs ⁻¹	[13]
Ppy-G	1000	91%	1 A g ⁻¹	[14]
GO 3	1000	98%	10 A g ⁻¹	This work

5. Determination of Capacitive and diffusion controlled contribution

The ratios of capacitive and diffusion were calculated according to the reported method¹⁵ using an equation below.

$$i(V) = k_1 v + k_2 v^{1/2}$$

$k_1 v$ and $k_2 v^{1/2}$ correspond to the current contributions from the surface capacitive effects and the diffusion-controlled process, respectively.

Table S5. Calculation of Capacitive and diffusion controlled contribution for **GO 3** at 100 mV/sec.

Specific potential	Capacitive charge storage	Diffusion charge storage
0.3 V	71.6 %	29.4 %
0.4 V	62.3 %	37.7 %
0.5 V	64.3 %	35.7 %
0.6 V	82.4%	17.6 %

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